

## CLAIMS

What is claimed is:

1. A pellicle, wherein a total weight of a volatile organic compound to be detected is not more than 0.5 ppm based on the pellicle weight when an organic compound component generated from the pellicle is collected at a room temperature of 26°C for 24 hours under a nitrogen flow of 100 ml/min, the organic compound component collected under the nitrogen flow is adsorbed by a porous polymer beads adsorbent based on 2,6-diphenyl-p-phenylene oxide, the adsorbed organic compound component is heated at 260°C for 15 minutes so that the organic compound component is thermally desorpted from the adsorbent in a gas form, and the thus-generated gas is analyzed.
2. A method of manufacturing a pellicle, wherein a total weight of a volatile organic compound to be detected is not more than 0.5 ppm based on the pellicle weight when an organic compound component generated from the pellicle is collected at a room temperature of 26°C for 24 hours under a nitrogen flow of 100 ml/min, the organic compound component collected under the nitrogen flow is adsorbed by a porous polymer beads adsorbent based on 2,6-diphenyl-p-phenylene oxide, the adsorbed organic compound component is heated at 260°C for 15 minutes so that the organic compound component is thermally desorpted from the adsorbent in a gas form, and the thus-generated gas is analyzed,  
wherein an act of removing the volatile organic compound from the pellicle is carried out.
3. The method of manufacturing the pellicle according to claim 2, wherein an act of removing the volatile organic compound from a member used for manufacturing the pellicle is carried out.

4. A pellicle-fed photo-mask with a pellicle being mounted thereon, wherein a total weight of a volatile organic compound to be detected is not more than 0.5 ppm based on the pellicle weight when an organic compound component generated from the pellicle is collected at a room temperature of 26°C for 24 hours under a nitrogen flow of 100 ml/min, the organic compound component collected under the nitrogen flow is adsorbed by a porous polymer beads adsorbent based on 2,6-diphenyl-p-phenylene oxide, the adsorbed organic compound component is heated at 260°C for 15 minutes so that the organic compound component is thermally desorbed from the adsorbent in a gas form, and the thus-generated gas is analyzed.

5. A method of manufacturing a semiconductor device using a photo-mask in a state that a pellicle is mounted thereon, wherein a total weight of a volatile organic compound to be detected is not more than 0.5 ppm based on the pellicle weight when an organic compound component generated from the pellicle is collected at a room temperature of 26°C for 24 hours under a nitrogen flow of 100 ml/min, the organic compound component collected under the nitrogen flow is adsorbed by a porous polymer beads adsorbent based on 2,6-diphenyl-p-phenylene oxide, the adsorbed organic compound component is heated at 260°C for 15 minutes so that the organic compound component is thermally desorbed from the adsorbent in a gas form, and the thus-generated gas is analyzed.

6. A method of using a pellicle, wherein a total weight of a volatile organic compound to be detected is not more than 0.5 ppm based on the pellicle weight when an organic compound component generated from the pellicle is collected at a room temperature of 26°C for 24 hours under a nitrogen flow of 100 ml/min, the organic compound component collected under the nitrogen flow is adsorbed by a porous

polymer beads adsorbent based on 2,6-diphenyl-p-phenylene oxide, the adsorbed organic compound component is heated at 260°C for 15 minutes so that the organic compound component is thermally desorbed from the adsorbent in a gas form, and the thus-generated gas is analyzed,

wherein the pellicle is used for preventing dust in a process of manufacturing a semiconductor device.